

<b>Form 1449 (Modified)</b>  <b>Information Disclosure Statement By Applicant</b>  (Use Several Sheets if Necessary)	Atty. Docket No. HIT1P057/ HSJ920030250US1 Applicant: Guthrie et al. Filing Date: Herewith	Application No.: Unassigned  Group Art Unit: Unassigned

**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
ADT	1	2003/0184912	10/02/2003	Hsiao et al.	360	123	04/02/2002
	2	2003/0135986	07/24/2003	Eschbach et al.	29	603.12	01/14/2002
	3	2003/0104770	06/05/2003	Pasqualoni et al.	451	60	04/30/2001
	4	2003/0104699	06/05/2003	Minamihaba et al.	438	692	11/26/2002
	5	2003/0079416	05/01/2003	Ma et al.	51	307	08/17/2001
	6	6,554,878	04/29/2003	Dill, Jr. et al.	51	308	06/14/1999
	7	6,510,022	01/21/2003	Lahiri et al.	360	126	02/15/2000
	8	6,508,953	01/21/2003	Li et al.	252	79.1	10/19/2000
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**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
ADT	18	2003100678	2003-04-04	JP	H01L	21/304		
ADT	19	2001031953	2001-02-06	JP	C09K	3/14		

**Other Documents**

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
ADT	20	Yoshimizu, H., et al., "Thin Film Magnetic Film Head Composed of Inorganic Materials," IEEE Transactions on Magnetics, Volume 28, No. 5, September 1992
	21	"Alkaline Formulations for Chemical Mechanical Polishing of Copper Utilizing Azole Passivation", IBM Technical Disclosure Bulletin, October 1994
ADT	22	"Chemical-Mechanical Polishing of Copper with Ammonium Persulfate", IBM Technical Disclosure Bulletin, October 1994
	23	
Examiner /A. Dexter Tugbang/		Date Considered 11/2/06

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.